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Claim 16. (previously amended) The method of claim 1 wherein the polymer is a negative resist.

Claim 17-30. (cancelled)

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Claim 31. (currently amended) A method of forming a positive or negative photoresist relief image, comprising:

(a) applying a coating layer of a photoresist composition of claim 17 on a substrate,   
the photoresist composition comprising a photoactive component and a resin comprising a polymer that comprises repeat units of:

1) an active methylene or aldehyde or other carbonyl compound that forms an acetal group in a polymerization or co-polymerization reaction; and

2) a polyol or thiol that reacts with the methylene or aldehyde or other carbonyl compound to form the acetal group; and

(b) exposing and developing the photoresist layer to yield a positive-tone relief image, wherein the photoresist layer is exposed with radiation having a wavelength of less than about 300 nm.

Claims 32-37. (cancelled)

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